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Design and simulation of a smart bottle with fill-level sensing based on oxide TFT technology

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"The beginning of wisdom is found in doubting; by doubting we come to the question, and by seeking we may come upon the truth."

Pierre Abelard









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Abstract

Packaging is an important element responsible for brand growth and one of the main reasons for producers to gain competitive advantages through technological innovation. In this regard, the aim of this work is to design a fully autonomous electronic system for a smart bottle packaging, being integrated in a European project named ROLL-OUT. The desired application for the smart bottle is to act as a fill-level sensor system in order to determine the liquid content level that exists inside an opaque bottle, so the consumer can exactly know the remaining quantity of the product inside.

An in-house amorphous indium—gallium—zinc oxide thin-film transistor (a-IGZO TFT) model, previously developed, was used for circuit designing purposes. This model was based in an artificial neural network (ANN) equivalent circuit approach.

Taking into account that only n-type oxide TFTs were used, plenty of electronic building-blocks have been designed: clock generator, non-overlapping phase generator, a capacitance-to-voltage converter and a comparator. As it was demonstrated by electrical simulations, it has been achieved good functionality for each block, having a final system with a power dissipation of 2.3 mW (V_{DD} =10 V) not considering the clock generator. Four printed circuit boards (PCBs) have been also designed in order to help in the testing phase.

Mask layouts were already designed and are currently in fabrication, foreseeing a successful circuit fabrication, and a major step towards the design and integration of complex transducer systems using oxide TFTs technology.

Keywords: Smart packaging; a-IGZO TFTs; capacitance-to-voltage converter; comparator; oxide TFTs circuit integration.





Resumo

As embalagens são um elemento importante no crescimento de determinadas marcas e uma das principais razões pelas quais certos produtores ganham vantagem competitiva através de inovações tecnológicas. Neste âmbito, o objetivo deste trabalho corresponde ao desenvolvimento de um sistema eletrónico totalmente autónomo para uma garrafa inteligente, estando este integrado num projeto europeu designado de ROLL-OUT. A aplicação pretendida da garrafa, é que esta contenha um sistema sensível ao nível de enchimento do liquido da mesma, de forma a que o consumidor possa determinar, de forma exata, a quantidade restante de produto existente dentro de uma garrafa opaca.

Para o propósito de desenho de circuitos, foi usando um modelo de transístores de filme fino baseados em óxido de gálio-índio-zinco amorfo (a-IGZO TFTs), sendo que o mesmo fora anteriormente desenvolvido. Este modelo foi baseado numa aproximação de circuitos equivalentes através de redes neuronais artificiais.

Tendo em conta que apenas transístores do tipo-n foram utilizados, foram desenvolvidos vários blocos eletrónicos: gerador de relógio, gerador de fases não sobrepostas, conversor capacidade/tensão e um comparador. Tal como foi demonstrado através de simulações elétricas, foi alcançada uma boa funcionalidade para cada bloco, tendo-se obtido um sistema final com uma dissipação de potência de 2.3 mW (VDD=10 V), não considerando o gerador de relógio. Foram ainda desenvolvidas quatro placas de circuito impresso com o objetivo de futuramente auxiliar o teste dos circuitos produzidos.

Os layouts das máscaras já foram desenvolvidos estando neste momento em fase de fabricação, prevendo-se assim uma produção de circuitos bem-sucedida, e um grande passo no desenvolvimento e integração de sistemas transdutores complexos usando a tecnologia de transístores de óxidos semicondutores.

Palavras-chave: Embalagens inteligentes; a-IGZO TFTs; conversor capacidade/tensão; comparador; integração de circuitos com transístores de óxidos.









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Symbols

- Cox Gate oxide capacitance per unit area
- G_m Transconductance of a transistor
- I_{DS} Current between drain and source
- I_{GS} Current between gate and source
- L Channel length
- Q Capacitor charge
- r_0 Output resistance of a transistor
- V_{DS} Voltage between drain and source
- V_{GS} Voltage between gate and source
- V_{IH} Input high voltage
- V_{IL} Input low voltage
- V_{OH} Output high voltage
- Vol Output low voltage
- V_{ON} Turn-on voltage
- Vos Voltage offset
- V_T Threshold voltage
- W Channel width
- μ_{FE} Field-effect mobility
- μ_{SAT} Saturation mobility
- λ Channel-length modulation parameter
- Φ_1 Phase one
- Φ_2 Phase two









Acronyms

a-IGZO - Amorphous indium-gallium-zinc oxide

a-Si- Amorphous silicon

a-ZTO - Amorphous zinc-tin oxide

ANN - Artificial Neural Network

CEMOP - Center of Excellence in Microelectronics Optoelectronics and Processes

CMOS - Complementary metal-oxide-semiconductor

CVD - Chemical vapor deposition

C/V - Capacitance-to-voltage

DRC - Design rule check

EC - Equivalent circuit

FET - Field-effect transistor

IT – Information technology

LCD - Liquid-crystal display

LTPS - Low temperature polycrystalline silicon

MOSFET - Metal-oxide-semiconductor field-effect transistor

OTFT - Organic thin-film transistor

PCB - Printed circuit board

PDK - Process design kit

Poly-Si - Polycrystalline silicon

RT – Room temperature

SMU - Source measure unit

TCO - Transparent conductive oxide

TFT -Thin-film transistor

TSO - Transparent semiconducting oxide

UNINOVA - Instituto de desenvolvimento de novas tecnologias









1 Motivation and Objectives

In the last years, the huge development of transparent conducting oxides (TCOs) and transparent semiconducting oxides (TSOs) have opened the door to a new era of transparent and flexible electronics based on oxide thin-film transistors (TFTs). This technology has been gaining a paramount importance in almost every field where it can be applied on, such as fully transparent displays, smart windows and watches or even wearable electronics [1]–[6]

The aim of this work is to design a fully autonomous electronic system for a smart bottle packaging and it is integrated in a European project named ROLL-OUT. The goal of the ROLL-OUT project is to create a multi-purpose technology for, thin, large-area, high-performance, smart, and autonomous systems comprising integrated circuits, sensors, electronics, advancing packages, automotive interiors and textile industries beyond their traditional scope.

The ROLL-OUT project is envisioned to have direct impact on manufacturing capability and value-addition of consumer goods in Europe. The project consortium partners are from various section of the large-area, flexible systems industry value chain being some of them: UNINOVA, VTT, IISB, CIDETEC, PICOSUN, LOGOPLASTE and POLYTEKNIK. The work presented in this document is thus part of UNINOVA's contribution for the project, aiming the design and simulation of integrated circuits (where the main blocks can be identified in figure 1.1) based on models developed for amorphous indium-gallium-zinc oxide (IGZO) TFTs produced at low temperature (180

°C) on flexible substrates. Other partners of the project develop in lab scale the remaining components of the final smart bottle, namely capacitive sensors and printed batteries, which are then trasfered to industrial partners for fabrication in large scale roll-to-roll systems. All these components are developed according to the requirements of a bottle specifically designed for this project by the partner Logoplaste Innovation Lab.

Packaging is an important element responsible for brand growth and the main reason for producers to gain competitive advantages through innovation, and is leading companies to look with evermore interest for the integration of sensors capable of giving a clear feedback on the shelf life of the products.

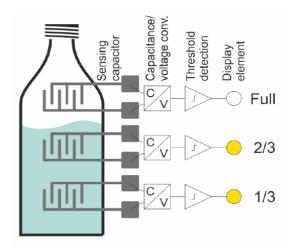


Figure 1.1- Scheme of the smart bottle functioning principle and the main electronic blocks.





The desired application for the specific smart bottle designed here is to act as a fill-level sensor system to determine the liquid content that exists inside the bottle and to be used by any market segment. This would allow the consumer to know exactly the remaining quantity of the produce inside and/or identify habits of consumption. Naturally, the blocks designed here can then be adapted for many other market segments where functionality provided by flexible thin-film electronics is desired.





2 Introduction

In this chapter an introductory background will be summarized, giving special focus to the TFTs structure, operation principle, and also their technological evolutions. It will be also briefly explained the functionality and typical structure of the main electronic blocks used in the smart bottle system, namely the capacitance-to-voltage converter and the comparator.

2.1 Thin-Film Transistors

In a world of constant technology evolution, there are always common goals in almost every scientific field, like reducing costs, achieving better performance, having less power consumption and creating technological innovations.

Nowadays one of the major researching themes is transparent and flexible electronics, in which TFTs acquire an important role due to their advantages over the existing transistors technology, which will be presented further.

2.1.1 TFTs structures and operation principle

A TFT is basically a field-effect transistor (FET) composed, by three terminals named gate, source and drain, a semiconductor and a dielectric layer, just like a standard metal-oxide-semiconductor field-effect transistor (MOSFET). The semiconductor is located between the source and drain contacts and the dielectric is placed between the gate electrode and the semiconductor layer.

TFTs are more focused on large area and low processing temperature electronics, while the regular MOSFET technology main prominence is to achieve high performance devices, although it needs high processing temperatures.

The working principle of a TFT consists in the modulation of the current that flows between the drain and source contacts (I_{DS}) by applying a potential between the gate and source (V_{GS}), therefore the modulation is achieved by a capacitive injection of carriers close to the dielectric/semiconductor interface [7].

TFTs can have several structures, the most common ones can be observed in figure 2.1. The structure's name depends whether the source/drain and gate electrodes are on the same or opposite side of the semiconductor, being identified as coplanar or staggered structure respectively.

For each of these two structures, top- or bottom-gate configurations can also be defined, depending on whether the gate is on top or bottom of the device. For example, in active matrices





of liquid-crystal displays (LCDs), the staggered bottom-gate configuration is preferred since the typically used a-Si:H TFTs are light sensitive and this structure allows the shielding of the semi-conductor by the metal gate electrode. Conversely, in poly-Si TFTs, a coplanar top-gate structure (where the semiconductor is first deposited) is generally preferred, since the semiconductor crystallization process requires high temperatures that can damage and degrade other layers previously deposited.

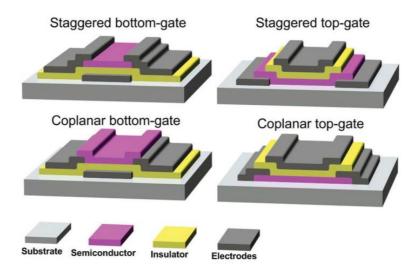


Figure 2.1- Scheme of the most conventional TFT strutures, according to the position of the gate electrode and sorce/drain electrodes relatively to the semiconductor, adapted from [7].

In terms of operating principle, considering an n-type TFT, the positive or negative value of the threshold voltage (V_T) will dictate if the transistor is in enhancement or depletion mode respectively. Generally the enhancement type transistors are preferred since no V_{GS} is needed to turn off the transistor, simplifying the circuit design and minimizing power dissipation [8].

When $V_{GS} \ll V_T$ the transistor dielectric/semiconductor interface is depleted of electrons and negligible current flows, resulting in the Off-state.

When V_{GS} > V_T the dielectric layer acts like a capacitor, so that in the semiconductor channel and opposing negative charge is induced, creating a conductive channel that allows the electrons flow from the source to the drain, designated as the On-state. The magnitude of the current depends on a few number of parameters like the width and length of the TFT, the capacitance of the gate insulator per unit area and the properties of the semiconductor and dielectric layer [9].

As it can be observed in figure 2.2, in the On-state, there are two regimes depending on the value of the voltage between source and drain (V_{DS}). When $V_{DS} < V_{GS} - V_T$ the TFT is in the linear regime, meaning that I_{DS} increases linearly with the applied V_{DS} . In this case the drain current can be expressed by:





$$I_{DS} = \mu_{FE}. C_{ox} \times \frac{W}{L} \left((V_{GS} - V_T) V_{DS} - \frac{V_{DS}^2}{2} \right)$$
 (1)

Where μ_{FE} is the field-effect mobility in cm²/(V.s), C_{ox} is the oxide capacitance in F/cm² and W and L are the TFT channel width and length.

On the other hand, if $V_{DS} > V_{GS^-} V_T$ the semiconductor close to the drain region becomes depleted and a phenomenon designated by pich-off occurs leading to the saturation mode, where ideally I_{DS} is independent of V_{DS} and the current can be expressed by:

$$I_{DS} = \frac{\mu_{sat} \cdot C_{ox}}{2} \times \frac{W}{L} (V_{GS} - V_T)^2$$
 (2)

Although, when the drain voltage becomes too high, or the channel length becomes too short, non-ideal effects can arise, such as I_{DS} increase with V_{DS} in saturation mode, a phenomena called channel-length modulation [10]. To take this effect into account equation (2) can be modified as follows, where λ is the channel-length modulation parameter:

$$I_{DS} = \frac{\mu_{sat}. C_{ox}}{2} \times \frac{W}{L} (V_{GS} - V_T)^{-2} \times (1 + \lambda. V_{DS})$$
 (3)

2.1.2 TFTs technology evolution

As mentioned above, TFTs are fundamental building blocks for today's breakthroughs in microelectronics, like plastic based flat-panel displays, wearable computers or even paper electronics [11]–[13]. So it is quite expected, and noticeable that the scientific research on this topics has greatly increased since these last few years [7].

There are different technologies in which the TFTs are based on, for instance, organic thin-film transistors (OTFTs) have been intensively researched, because of their properties allowing to reduce the processing temperature and cost when compared to a-Si TFTs, giving also the possibility to perform roll-to-roll manufacturing [14]. Nonetheless, the relatively low mobility and

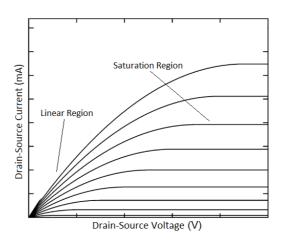


Figure 2.2- Ideal output curves of a n-type TFT, adapted from [37].

poor bias stability of a-Si and organic TFTs may limit their practical usage in some applications. In low-temperature poly-Si (LTPS) it is possible to achieve values of mobility up to 100 cm²/V.s





and excellent device stability, but it requires a high temperature processing as well as an expensive crystallization and doping process, which prevent the use of plastic substrates [15].

In this regard, metal oxide TFT technology has recently gained considerable importance, due to its high mobility, low temperature processing, good transparency to visible light, low power consumption, faster response times and relatively low fabrication cost [7].

Therefore, oxide TFTs potentiate a significant cost reduction from poly-Si TFTs, since these can be fabricated without needing a crystallization or doping process. It can be observed in table 2.1 a brief review of the TFT main parameters for the technologies aforementioned.

Table 2.1- Comparison between some of the main characteristics for the different types of TFTs technologies based on [14], [16]–[18]

	LTPS TFT	a-Si TFT	Organic TFT	Oxide TFT
Stability	High	Low	Low	High/medium
Mobility (cm²/V.s)	< 100	< 1	< 10	10-60
Yield	Medium	High	High	High
Deposition Technique	CVD+Exci-	PECVD	Printing or vacuum	Sputtering or
	mer Laser		evaporation	printing
Processing Temperature	< 500	250 - 350	RT	RT - 300
(°C)				
Substrate	Glass or	Glass,	Glass, Metal or	Glass, Metal or
	Metal	Metal or	Plastic	Plastic
		Plastic		

Considering all the oxide TFT technology features mentioned, it is understandable why this technology created such a big research interest all over the world. The mainstream and most optimized oxide TFTs are the ones based in amorphous indium-gallium-zinc oxide (a-IGZO). In fact, since the initial work on IGZO TFTs of Prof. Hosono's group in Tokyo Institute of Technology in 2004, many laboratories and industries around the world adopted this material for developing TFTs. In 2010, C. J. Chiu et al. produced an a-IGZO TFT using Ta₂O₅ as gate dielectric that had a high field-effect mobility of 61.5 cm²/V.s, a subthreshold voltage swing of 0.61 V/decade and a current on/off ratio of 10⁵ making it suitable for use as a switching transistor in low-power applications [19].

However, different oxide materials are in constant research in TFT application, for example regarding the fabrication of TFTs using economically sustainable materials, as the ones without indium in its multicomponent oxide composition. In this regard, H. Q. Chiang et al. fabricated in 2005 the first amorphous zinc-tin oxide (a-ZTO) based TFTs that when annealed at 300 °C had field-effect mobilities between 5 and 15 cm²/V.s and a on/off current ratio greater than 10⁷ [20].





Another approach that has been considered to simplify and reduce processing costs is the fabrication of TFTs by printing the layers with a solution based precursor. The standard methods used for producing electronic devices are based on the sequential deposition, patterning and etching of different layers, involving mostly vacuum-based technologies, which contribute to a high manufacturing cost. Direct printing of inorganic materials allows to deposit films using a direct additive patterning process, enabling high-performance and low-cost electronics. The main issue in this kind of approach is the difficulty in preparing ink-jet-printable precursors conjugated with a desired performance, however in this process no masks or screens are needed and since it is an additive process, materials are applied only where desired. When using direct printing a cpst reduction of 64% is achieved when compared to the standard microelectronics technologies [7].

K.K. Banger et al. were able to fabricate a reproducible and high operationally stable IGZO solution-processed TFTs with field-effect mobilities of 10 cm²/V.s and a subthreshold slope of 0.42 V/decade, plus the devices fabrication was made with a maximum temperature of 230 °C allowing the future integration of this technology with flexible substrates [21].

There is also a lot of research in the development of p-type oxide TFTs since these have instability issues and are very limited by the low hole mobility. When high performance p-type TFTs are obtained a new era of oxide-based electronics certainly will arise, by allowing the production of complementary metal-oxide-semiconductors (CMOS) which is the core for the microelectronics of information technology (IT), permitting the use of compact and ultra-low power consumption circuitry [7].

All the referred topics lead to a huge capability of circuit integration using oxide TFTs technology, in this regard the next subsections will briefly explain the functionality of the most important electronics blocks used in the smart bottle system.

2.2 Capacitance-to-voltage converters

Capacitance is one of the most broadly used parameters in sensors applications, therefore many circuits have been developed to convert capacitance variations into measurable electric signals. This kind of circuitry is widely used in several scientific fields, for example, in the measurement of physical quantities such as density, force or even blood pressure and component concentration in multicomponent fluids [22]–[24]. This electronic circuit is denominated as a capacitance-to-voltage (C/V) converter, and when attached to a capacitive sensor they form an electrically measurable capacitive transducer.

C/V converters can be based on direct or indirect conversion methods. In the direct method the capacitance is directly converted into voltage while in the indirect it first occurs a conversion into frequency or time and only then the conversion to voltage [25].

Although the indirect conversion-based C/V converters are more accurate and sensitive they need some relatively complex circuitry attached, since the output frequency, that is proportional to the capacitance, still needs to be converted into voltage.





Since this project aims to use simple, high yield but still reliable and functional circuits it was adopted a direct type C/V converter based on a charge distribution method

It is important to emphasize that to the author's knowledge there are no reports in literature regarding the use of oxide TFTs in designing any type of C/V converter.

2.3 Comparators

The comparator is one of the most important blocks since early electronic developments. The main function of this block is to compare two analog input voltage levels and produce an output digital signal that depends in the magnitude of both. A comparator is basically used whenever a comparison of voltages or currents is needed, for example in zero-crossing detectors, relaxation oscillators, level shifters or analog-to-digital converters [26]–[28].

The following equation and voltage transfer curve represents the real functioning of a comparator, i.e. without an infinite gain.

$$V_{out} = \begin{cases} V_{OH}, & if \ (V_{in}^{+} - V_{in}^{-}) > V_{IH} \\ A_{v}(V_{in}^{+} - V_{in}^{-}), & if \ V_{IL} < (V_{in}^{+} - V_{in}^{-}) < V_{IH} \\ V_{OL}, & if \ (V_{in}^{+} - V_{in}^{-}) < V_{IL} \end{cases}$$
(4)

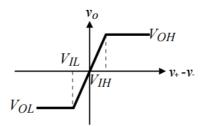


Figure 2.3- Voltage transfer characteristic of a comparator with infinite gain, adapted from [27].

The main static and dynamic characteristics of a comparator are: gain, output voltage in high and low states, input voltage offset, noise, hysteresis, propagation delay time and the slew rate [27]. However, in this project the main focus will be the input voltage offset, since it is one of the most critical characteristic for the desired final application, as long as the other characteristics remain between acceptable values. The voltage offset (V_{OS}) corresponds to the input voltage difference necessary to make the output equal to the mean value between the output high and low state, this offset depends on the circuit devices mismatches and can be reduced be several autozeroing techniques. In general, when not using autozeroing techniques, the voltage offset value is about tens of millivolts [30].

The adopted comparator architecture in this project consists in two cascaded high-gain pre-amplifying stages followed up by a simple latch as it will be demonstrated later on.





3 Materials and Methods

3.1 Modelling, Design and Simulation Tools

This project was realized using an in-house TFT model that was performed using artificial neural network (ANN) based equivalent circuits (EC) to predict static and dynamic behavior of the devices. To build the model, measurements were previously done in order to extract the devices main parameters, then an EC is derived from the devices structure and each electrical element in it is modeled with an ANN. Lastly these networks are implemented in Verilog-A [29].

The main software used in this project was Cadence Design Systems, allowing to perform the schematics and layout design and the respective simulations, using VirtuosoTM Platform and SpectreTM Simulator.

For the layouts design, it was used an in-house process design kit (PDK) based on the existing fabrication processes limitations and adapted to the optical lithography constrains available at CEMOP/UNINOVA, considering a safety misalignment factor to prevent undesirable effects. Along other feautures, the PDK includes both design rule check (DRC) and layout versus schematic (LVS) verification decks.

The DRC determines if a layout satisfies a series of recommended parameters called design rules, imposed by the fabrication processes. The rules used for each layer, during the circuit layout are presented in A annex.

LVS is a method of verifying that the layout of the design is functionally equivalent to the respective schematic, i.e. if they have the same electrical connections and therefore the schematic can be obtained from the layout.

In this project it was also used CadSoft EAGLE design software, in order to design the printed circuit boards (PCBs) needed to help in the testing phase and in the circuit debugging of the smart bottle system. In this regard, four PCBs where designed and also a custom layout for a peripheral component interconnector (PCI) enabling to connect the glass of the produced circuit with the respective testing PCB.





3.2 Electrical characterization of transistors and circuits

Since the future step of this work is to test the whole involved devices and building blocks of the system, electrical characterization is of major importance. For this purpose, the transfer and output curves of the different sized TFTs will be performed in ambient conditions, inside a faraday cage, using an Agilent 4155C semiconductor parameter analyzer connected to a Cascade Microtech M150 manual microprobe station, controlled by the software Metrics ICS. The Agilent measurements can be performed with different ranges depending on the testing circuit.

Capacitance versus voltage plots will also be performed in order to extract the devices parasitic capacitances and cross-check with the values considered in the electrical model, for this end a semiconductor parameter analyzer (Keithley 4200-SCS) together with a probe station (Keithley 4200-SCS), in ambient conditions, will be used.





4 Results and Discussion

This chapter discusses the results regarding the design and the electrical simulations of all the necessary building-blocks to implement the smart bottle system, being divided in three main sections; in the first one an overview of the system is given as well as an explanation of what ideally happens to the electrical signal in each block; in the second section the emphasis is given to the design and layout of the blocks described before, where simulation results using the IGZO TFT model are described; the last section is dedicated to the design of the schematics and layouts of the four testing PCBs.

4.1 Fill level sensing in smart bottle: Concept and Block Diagram

It is important to refer that the final adopted system topology presented results from the discussion among the partners of the project, having the common objective of producing simple and cheap circuits. It was also imperative to keep the transistor count as low as possible in order to maximize yield during the future processing of the circuits in lab-scale.

In figure 4.1 it is presented the block diagram of the full smart bottle system. The system only needs a supply voltage in order to start operating. Firstly, a clock signal is generated by the 23-stage ring oscillator being then its frequency divided by a factor of 16 imposed by the D-type flip-flop 4-bit counters. These two blocks represent the clock generator. Then, the produced clock signal is applied to the input of the clock-phase generator that consequently generates two non-overlapping phases at the output. These two non-overlapping phases serve as inputs of the C/V converter whose output response will depend on the capacitive sensor value (more details in the following section).

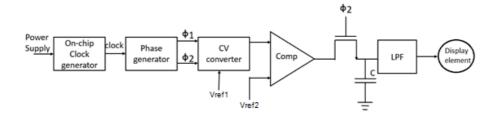


Figure 4.1- Block diagram of the full fill-level sensing smart bottle system.





In the comparator, first an amplification of the differential voltage between the two inputs occur. Then the latch gives an output of V_{DD} or V_{SS} depending on which input has a higher voltage value. The reference voltage value of the comparator was chosen in order to be between the voltage values obtained at the output of the C/V converter in each scenario (either with or without liquid). Hence, when there is no liquid in the capacitive sensor, the output signal of the C/V converter is always lower than the reference voltage resulting in the low state of the comparator. On the other hand, when there is liquid in the sensor, a capacitance gain occurs in the sensor resulting in a higher voltage and in the high state of the comparator.

After the comparator a switch fed by phase two is used in order to only sample the voltage comparison in this same phase, where the signal actually depends on the sensor capacitance unlike phase one (more details given in the next section).

In the last stage a low-pass filter is implemented in order to eliminate high frequency components that may arise and degrade the circuit performance. Finally, the signal reaches a display element which depending on the applied voltage can be either in on or off state, i.e. illuminated or not.

The smart bottle has an active area of $1.8 \times 10 \text{ cm}^2$, in which three independent systems will be implemented allowing the control of three different electrochromic cells, as presented in figure 1.1. Also, the whole system will operate at a frequency of few kHz.

All the above-mentioned functional blocks will be explained, in detail, in the next section.

4.2 Circuit design, simulations and layouts

As stated before, based on the aforementioned concept all the necessary building blocks were designed and simulated using Cadence Design Systems, being ordered in this section following a gradual increase in the complexity.

It is important to mention that in complex circuits using TFTs, some parameters variations can dramatically affect the circuit performance, like the turn-on voltage (V_{ON}) and also the gate leakage current (I_G). In the main used model, the TFTs presented a V_{ON} of -0.5V, but in order to guarantee a high circuit robustness, simulations were also performed using a V_{ON} of 0.5V.

Passive elements were not considered in the design due to the high device mismatch when these are produced in clean room environment. Also, all the blocks were designed using only n-type oxide TFTs, due to the absence of reproducible and stable p-type ones.

Since the available active area of the bottle is relatively high, the die area was not an earlier concern. Instead, the TFTs dimensioning was made taking into account the functionality and simplicity of the building-blocks. In annex B a table is presented with all the considered TFTs dimensions.





The TFT structure in which the building-blocks are based can be observed in figure 4.2, where the source, drain and gate electrodes are made of a 60 nm thin film of molybdenum, the semiconducting layer is 35 nm thick IGZO and the dielectric is composed by a 100 nm multilayer of Ta₂O₅/SiO₂. All the layers are deposited and patterned, respectively, by sputtering and conventional photolithography techniques at UNINOVA and also a post-deposition annealing treatment at 180 °C. Fully fabrication details can be found in [30].

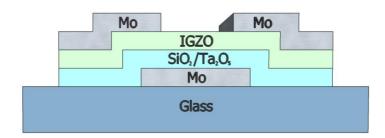


Figure 4.2- Staggered bottom gate structure of the IGZO TFTs, adapted from [30].

After the fabrication of the devices, an electrical characterization was performed, in which output curves and capacitance-voltage curves of the TFTs were measured. Subsequently, the TFTs model were previously designed, based on ANN like mentioned in 3.1.

Figure 4.3 shows the measured curves in which the model was based on, as well as the TFT model simulation. As it can be observed, the simulations show a good agreement (<5 % mean absolute relative error) with the corresponding measurements.

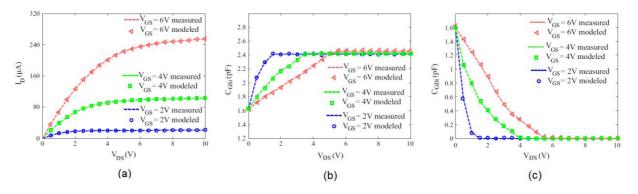


Figure 4.3- Verilog-A neural model performance validation from the measurements $0 \le VDS \le 10 \text{ V}$ in steps of 0.5 V and $2 \le VGS \le 6 \text{ V}$ in steps of 2 V.(a)- Output characteristics curvers of the TFT. (b)- C-V characteristics curves between gate and source (C_{GSi}) (c)- C-V characteristics curves between gate and source (C_{GDi}). Adapted from [29].

These devices are showing a V_{ON} of \approx - 0.5 V, a V_{TH} of 1.35 V, an on/off current ratio greater than 10^7 and a mobility around 20 cm²/V.s [29].





This previously developed model allows to properly simulate the building-blocks in which, all the circuits will have the same fabrication conditions as the TFTs from model.

4.2.1 Logic gates

Inverter

Regarding design, the inverter is one of the simplest but most important circuits in digital electronics domain. In this project, the inverters were designed using a diode-connected load and a driver TFT. The optimized size ratio between the driver and load TFTs to obtain maximum and minimum values of V_{OH} and V_{OL} respectively, and considering a V_{DD} of 10 V, was 4:1. Although, plenty of ratios were used depending on the final application of the inverter, i.e. if we simply want a signal inversion, or an output voltage regeneration. The simulation of this and other logic gates was done at a frequency of 1 kHz, since the desired operation frequency of the system is in the range of few kHz.

The schematic, simulation and layout of this block can be observed in figures 4.4 and 4.5.

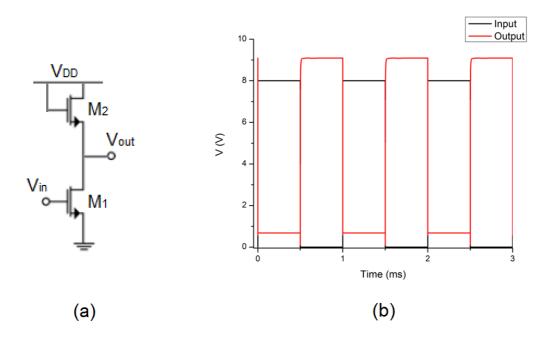


Figure 4.4- (a)- Circuit schematic of an inverter with a diode-connected load. (b)- Transient simulation result for the inverter considering the n-type load W/L= $10/20 \mu m/\mu m$ and driver W/L= $80/20 \mu m/\mu m$.





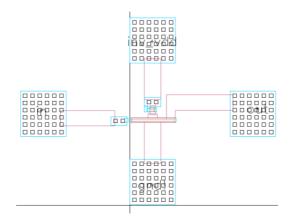


Figure 4.5- Layout of the inverter circuit.

In all the simulations the diode-connected transistor is operating in saturation mode (V_{DS} > V_{GS} - V_{T}).

In figure 4.2 it is presented the response of the inverter when a square wave is applied as input, considering a load transistor with $W=20~\mu m$ and $L=10~\mu m$ and a driver transistor with $W=80~\mu m$ and a $L=20~\mu m$, with a $V_{DD}=10~V$. Almost full swing of the output from near 0 V to $V_{DD}-V_{T}$ was observed for all the voltages, specifically presenting a high output voltage of 9 V, and a low output voltage of 510 mV for a frequency of 1 kHz.

In figure 4.5 it is presented the layout of an inverter, containing all the input and output pads needed for the testing phase.

NAND gate

A NAND gate has been also designed, with two driving TFTs in series and one diodeconnected load. This logic gate only has a low output when both inputs are in high state, otherwise if any of the inputs is low the logic gate output will be high.

As before, the schematic, simulation and layout of this logic gate is presented in figures 4.6 and 4.7.





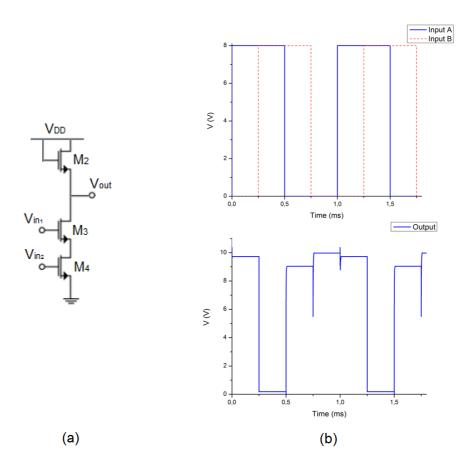


Figure 4.6- (a)- Circuit schematic of a NAND with a diode-connected load. (b)- Transient simulation result of the NAND considering the n-type load W/L= $10/20 \mu m/\mu m$ and drivers W/L= $80/20 \mu m/\mu m$.

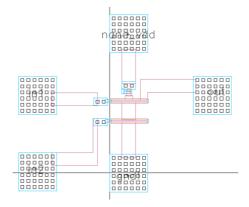


Figure 4.7- Layout of the NAND gate circuit.

In figure 4.6 it is presented the output response of a NAND gate considering a load transistor with $W=20 \mu m$ and $L=10 \mu m$ and both driver transistors with $W=80 \mu m$ and an $L=20 \mu m$,





with a V_{DD} =10 V. The simulation was performed applying two pulses as input (Vin_1 and Vin_2) with some delay relatively to each other, in order to have all the possible input combinations.

It can be observed on the simulated plots that the logic gate is behaving has expected, having a low output voltage only when the two inputs are high. It was obtained a high output voltage of 9.61 V and 9.92 V (there are two values resulting from the different input combinations that originate a high output voltage) and a low output voltage of 230 mV for a frequency of 1 kHz.

NOR gate

For the NOR logic gate the same simulation conditions were tested, but using two driving TFTs in parallel and diode-connected load with the same dimensions as in the NAND gate. This logic gate only has a high output state when both inputs are low. On the other hand, if one of the inputs is high the output will consequently be low.

The schematic, simulation and layout of this logic gate can be observed in figures 4.6 and 4.7.

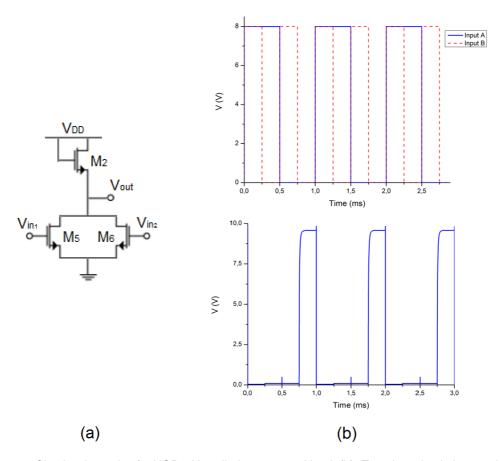


Figure 4.8- Circuit schematic of a NOR with a diode-connected load. (b)- Transient simulation result of the NOR considering the n-type load W/L= $10/20 \mu m/\mu m$ and drivers W/L= $80/20 \mu m/\mu m$.





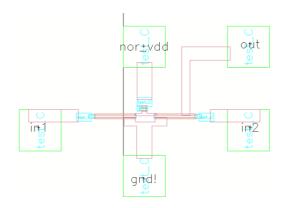


Figure 4.9- Layout of the NOR gate circuit.

The expected functionality of the NOR gate was achieved. For a frequency of 1 kHz, it was obtained a high output voltage of 9.82 V and a low output voltage of 230 and 340 mV depending on the different inputs combination that results in a low output value.

Overall, these simulated results demonstrate sharp transfer characteristics and a satisfactory functionality with operating frequencies up to tens of kHz. Although the operating frequencies are not as good as some other TFT technologies (particulary poly-Si owing to the intrinsically lower mobility of oxide semiconductors), some optimizations can be realized to allow higher operating frequencies, like scaling down the device dimensions, reducing the parasitic capacitances and the interconnections resistance.

Despite that, the TFTs have presented a very satisfactory performance, and viability in digital electronics for flexible and transparent electronic systems.

4.2.2 On-chip clock generator

Ring oscillator

A ring oscillator was designed to produce a square wave signal that will be used as the system clock. In this electronic block it's mandatory to always have an odd number of inverters to obtain an oscillation, otherwise the system would give a stable DC output value.

In this project it was designed a 23 stage ring oscillator like shown in figure 4.10. It can be also observed in figure 4.11 the respective layout of this block.





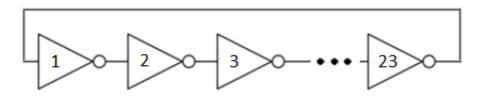


Figure 4.10- Scheme of a 23-stages ring oscillator.

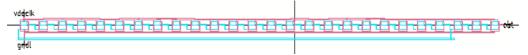


Figure 4.11-23-stages ring oscillator layout

With this topology and number of stages, a clock signal with an oscillation frequency of 50 kHz has been achieved. However, this frequency value is excessively high for the desired application, and some non-ideal effects may arise due to the response time of some electronic blocks. By adding more stages to the ring oscillator, it is possible to reduce the output frequency, but not significantly, so in order to decrease this value a frequency divider based on D-type flip-flops has been implemented. The usage of 23 stages in the ring oscillator allow to produce an output frequency which is not sufficiently high to degrade the performance of the counter itself, and also we were able to get complete rail-to-rail operation. In addition, with a very low number of stages we start to get a sine wave instead of a square one.

Frequency divider (D-type flip-flop counter)

As aforementioned, a D-type flip flop was design in order to be used as a frequency divider (counter), since the clock signal generated with the ring oscillator had an excessive frequency that could decrease the overall performance. The flip flop schematic and layout can be observed in figures 4.12 and 4.13. The 3-input NAND used, besides having another driving TFT in series with the other two, has the same schematic as the 2-input NAND already described above.

In order to make the flip-flop act as a counter, a simple feedback must be made, connecting the D input to the "not q" output, like shown on (b) in figure 4.12. Each counter will divide the frequency by a factor of 2. In this project a 4-bit counter was implemented by connecting four of the designed flip flops in series, resulting in a frequency division by a factor of 16.





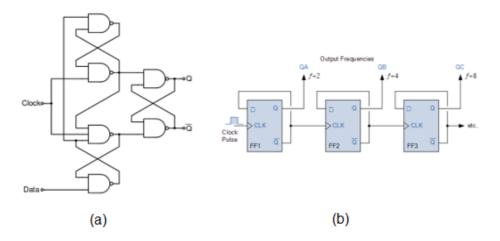


Figure 4.12- (a)- Circuit schematic of a D-type flip-flop. (b)- Scheme of the frequency divider feedback connections using a D-type flip-flop.

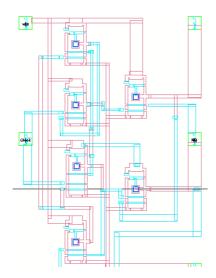


Figure 4.13- D-type flip-flop counter layout

To build the complete clock generator, the 23 stages ring oscillator was combined with the 4-bit counter frequency divider (figure 4.14), the simulation of this block is presented in figure 4.15.





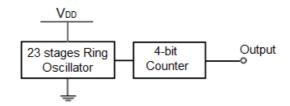


Figure 4.14- Scheme of the clock generator, comprising the ring oscillator and the 4-bit counter.

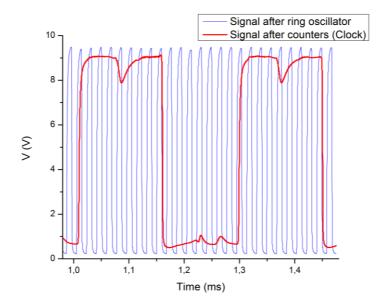


Figure 4.15- Simulation result of the 4-bit counter, when the signal generated by the ring oscillator is given as an input.

The blue line in the simulation represents the clock signal generated right after the ring oscillator, with a frequency of ≈ 50 kHz and the red corresponds to the clock signal after the 4-bit counter where it was achieved a final frequency of 3 kHz (i.e., frequency division by a factor of 16). The clock has a high voltage value of 9.2 V, and a low value of 0.7 V. The slight decay that occurs in the high voltage phase does not affect the circuit performance at all.

Two inverters were used at the end of this block with the objective of getting an output voltage regeneration.





4.2.3 Non-overlapping clock-phase generator

Since the capacitance-to-voltage converter needs two different input phases, a non-over-lapping clock-phase generator was also designed and implemented, whose schematic and layout can be observed in figures 4.16 and 4.17. This circuit is composed only by inverters and NOR gates. When a square signal is applied as the input, this block will generate two non-overlapping phases that are commonly used to perform the on/off commutation of transistors that act as switches.

More inverters can be added to the schematic in order to optimize the non-overlapping time.

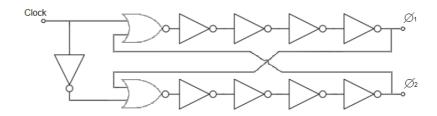


Figure 4.16- Circuit schematic of the non-overlapping clock-phase generator.

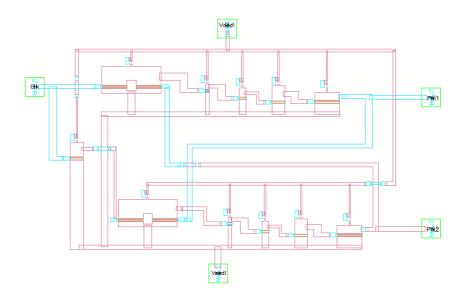


Figure 4.17- Layout of the non-overlapping clock-phase generator.





Figure 4.18 presents the phases generated by this block when a non-ideal input is given (i.e. the clock signal generated).

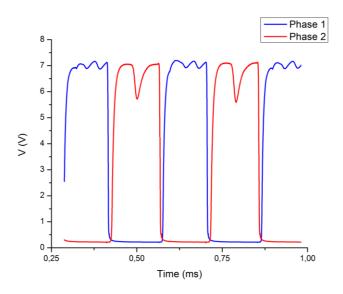


Figure 4.18- Simulation result of the non-overlapping phase generator when the clock signal is given as an input.

The phases have a "ON value" of 7 V and a "OFF value" of 300 mV. However, phase 2 has a little spike that arises from the input clock, but as before, this effect does not degrade the circuit performance since the values are not close to the ones necessary to enable the switches in the OFF state.

It is important to refer that in the cascaded inverters, the width of the driving TFTs was gradually increased by a factor of two, to properly regenerate the output and, simultaneously, increase smoothly the driving capability. Therefore, the widths (W) of the driving TFTs are (from the first cascaded inverter to the last one respectively) 40, 80, 160 and 320 μ m, whereas the length (L) is kept equal to 20 μ m to all of them.

4.2.4 Capacitance-to-voltage converter

This block is used to convert the different capacitance values from the sensor (with/without water) in readable voltage values that will be used as an input of the comparator.

. The schematic of the circuit can be observed in figure 4.19, it can be noticed the use of a reference capacitor and a sensor capacitor. It was decided to adopt this simple topology in order to decrease the circuit complexity of the system and also to improve the fabrication yield.





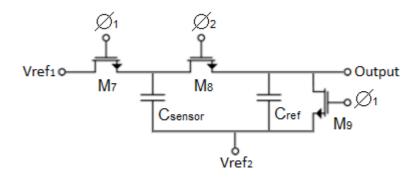


Figure 4.19- Circuit schematic of the capacitance-to-voltage converter proposed.

In table 4.1 it is presented the charge (Q) in each capacitor in both phase one and two.

Table 4.1- Representation of both capacitors charge in phase one and two.

	Phase 1	Phase 2		
Q _{Csensor}	C _{sensor} .(V _{ref1} - V _{ref2})	(Vout - Vref2).Csensor		
Q _{Cref}	0	(Vout - Vref2).Cref		

Knowing that a capacitor charge is equal to his capacitance times the voltage applied at its terminals, and also assuming that, between phase one and two charge conservation occurs, we obtain:

$$V_{out} = \frac{V_{ref1} - V_{ref2}}{1 + \frac{C_{ref}}{C_{sensor}}} + V_{ref2}$$
 (5)

Where C_{ref} , C_{sensor} , V_{ref1} and V_{ref2} represent, respectively the capacitance reference value, the sensor capacitance and the voltage reference one and two.

By plotting the equation presented it is possible to observe that, for the range of considered capacitance values, the output voltage variates linearly with the capacitance of the sensor.

In phase one the output voltage value is always sunk to V_{ref2} (analog ground), resulting always in the same DC voltage value, regardless of the sensor capacitance value. The charge distribution only occurs on phase two and in this same phase the output value depends on the sensor capacitance.

In figure 4.20 it is presented the simulation of this block where two possible scenarios are described, in (a) there is no water in the sensor, thus the sensor capacitance is 5 pF, and in (b)





there is water in the sensor allowing to have a capacitance gain of 100 % resulting in a capacitance of 10 pF. This capacitance variation allows to have an output voltage variation of about 400 mV, yielding a sensibility of ≈ 80 mV/pF.

By means of a parametric analysis, the chosen optimized value for the reference capacitor was 6 pF, since this was the one that could provide the biggest voltage variation at the output for the same sensor capacitor gain.

The layout of this block can be observed in figure 4.21.

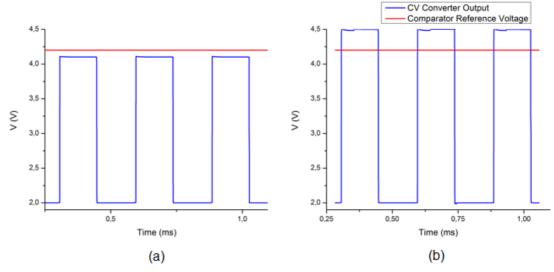


Figure 4.20- (a)- Transient simulation result of the C/V converter when there is no water in the capacitive sensor (5 pF). (b)- Transient simulation result of the C/V converter when there is water in the capacitive sensor (10 pF).

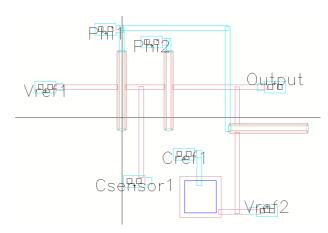


Figure 4.21- Layout of the C/V converter.





The red line represents the reference voltage of the comparator where it can be obviously seen that in the (a) scenario the capacitance-to-voltage converter output is always bellow this value but in the other hand in (b), in phase two, the output has a higher voltage value than the reference.

For the range of sensor capacitance (few pico-faradays) provided by one the project partners, a gain of 100 % was considered, i.e. the sensor capacitance goes from 5 to 10 pF, but the full system can discriminate the two different scenarios even with a gain of only 40 %.

4.2.5 Comparator

Latch

Being a latch part of the comparator, a simple one has been designed. It can be seen as a back to back connection of two inverters with positive feedback.

The latch schematic can be observed in figure 4.22 (a). Since the latch output is differential, there is a need to perform a dual to single-ended conversion, in which was used the simple circuitry presented in figure 4.22 (b). By representing the small-signal model of this converter it yields:

$$V_{out} = V_{in+} - V_{in-} \tag{6}$$

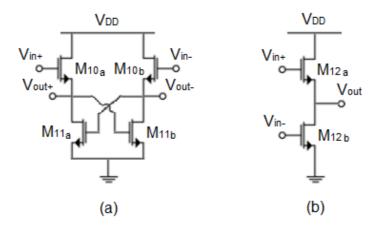


Figure 4.22- (a)- Circuit schematic of the latch. (b)- Circuit schematic of the doble to single-ended converter.

Depending on the values of each input, one of the outputs will tend to saturate to $V_{DD^-}V_T$ and the other to V_{SS} , i.e. when a differential signal is applied to the inputs of the latch, the output of the higher voltage side will be pulled up strongly than the other, and the positive feedback will cause this output to flip to the high state, consequently, the other side will be pulled to the low state, being possible to have a voltage discrimination.





The layout of the latch and the doble-to-single ended converter can be observed in figure 4.23.

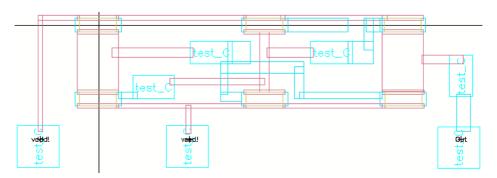


Figure 4.23- Layout of the latch and the doble-to-single ended converter

Positive feedback amplifier

Instead of using a regular common-source differential amplifier topology, it was adopted a topology that takes advantage of a positive feedback loop to significantly boost the gain. This topology schematic can be observed in figure 4.24 and it was adapted from [31].

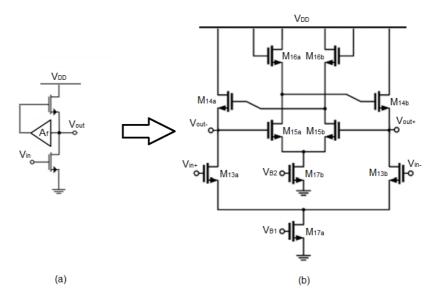


Figure 4.24- (a)- Circuit schematic of a regular common source amplifier having a positive feedback unit. (b)- Circuit schematic of the differential amplifier where the feedback network can be observed, adapted from [31].





By drawing the small-signal model of (a), and considering that $A_f \approx 1$, the gain can be express by:

$$\frac{Vout}{Vin} = -gm_{18} \times (ro_{18}//ro_{17}) \tag{7}$$

So this topology allows to have a much higher voltage gain when compared to a regular common-source differential amplifier, resulting in a better discrimination, thus a better comparison between similar voltage levels at the input of the comparator (i.e. the comparator have a lower offset voltage).

The main drawback of this topology is the decrease of the amplifier bandwidth, but in this particular case it doesn't bring any issues, since in the desired final application a low operation frequency will be used.

The simulations and the layout of the pre-amplifying block is presented in figures 4.25 and 4.26.

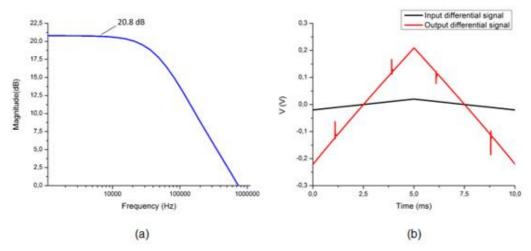


Figure 4.25- (a)- Bode magnitude plot of the differential amplifier. (b)- Simulation result of the differential amplifier output response with a differential triangular signal with 0.02V amplitude as input.





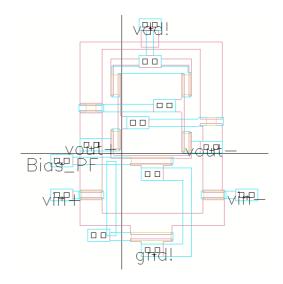


Figure 4.26- Layout of the positive-feedback amplifier.

In (a) it is presented the frequency response of the differential amplifier with positive feed-back, where it was possible to achieve an 11 V/V (20.8 dB) gain using 2 V as biasing condition, however the amplifier only present this gain when operating at frequencies in a range of few kilohertz. In (b) the input differential signal has an amplitude of 0.02 V, whereas the resulting output presents an amplitude of 0.22 V, being in accordance with the bode magnitude plot.

Complete comparator

The comparator is composed by a cascade of two positive feedback pre-amplifiers followed by an analog latch. The function of this block is to compare the voltage output value of the capacitance-to-voltage converter with a given reference, allowing to detect if there is, or not, water in the capacitive sensor.

As above-mentioned, the adopted high gain topology of the pre-amplifiers will help to better discriminate the values between the comparator voltage reference and the capacitance-to-voltage converter output by providing a good amplification between the differential signal.

In figure 4.27 it is presented the output reponse of the comparator when a differential input is given.





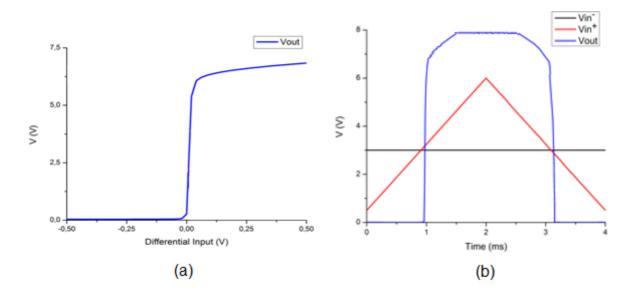


Figure 4.27- (a)- Simulation result of the comparator output when a differential voltage sweep is applied. (b)-Simulation result of the comparator output when a input triangular signal is applied.

The comparator presents a high output of 6.8 V (logic level "1") when *Vin*+ is higher than *Vin*-, and a nearly zero output in the other case.

It was achieved a good output swing for the desired application, so it is possible to discriminate which input of the comparator has a higher voltage value, allowing to directly know if we have, or not, water in the sensor. It was obtained a simulated systematic voltage offset value of 63 mV.

If higher accuracy was envisaged, the number of cascaded pre-amp stages could be increased, however, there is a limited active area that is allowed to be used on the bottle, so the increase of the die area must be taken into account.

4.2.6 Low-pass filter

A low-pass filter is very often needed in this kind of systems to eliminate high frequency components that may arise and degrade the circuit performance. This block was implement using a simple diode connected TFT acting as a resistive element and a simple capacitor, as it can be observed in figure 4.28.

In this topology the cut-off frequency is given by:

$$fc = \frac{1}{2\pi \times RC} \tag{8}$$





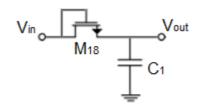


Figure 4.28- Circuit schematic of the low pass filter.

The following plot in figure 4.29 shows the frequency response of the low-pass filter. It has an enough cut-off frequency to prevent undesired high frequencies or huge spikes.

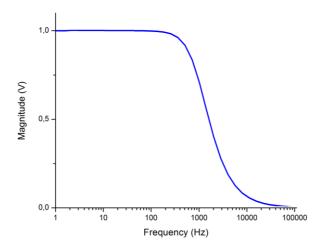


Figure 4.29- Bode magnitude plot of the low-pass filter.

4.2.7 Design of the complete system

In the previous sections it was already showed the output response of some blocks when actual circuit signals were given has input (i.e. not ideal signals). This section presents the simulation of the final system output in both with or without water scenarios, presented in figure 4.30.





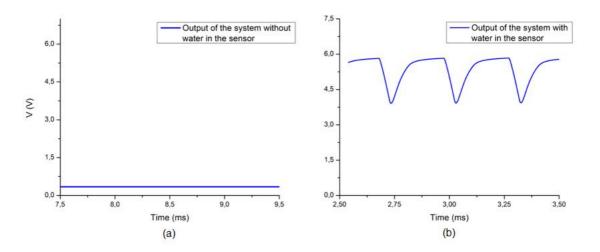


Figure 4.30- (a)- Result simulation of the final system output when there is not water in the capacitive sensor. (b)- Result simulation of the final system output when there is water in the capacitive sensor.

In (a) it is shown the output signal when there is no water in the sensor (C_{sensor} = 5 pF). The signal remains stable at about 300 mV, so it will result in the off state of the electrochromic cell. In (b) it is presented the output signal when there is water in the capacitive sensor (C_{sensor} = 10 pF). It can be seen that the output signal oscillates between 4 and 6 V. This oscillation occurs due to the switch after the comparator, which is supposed to sample phase two and hold in phase one but, since there is some circuit delay, it also samples the end of phase one which has a lower voltage. However, this decay does not affect in any aspect the circuit performance, since at these voltage ranges the electrochromic cells used as display elements are already saturated in terms of transmittance change and their response is considerably slower to turn visible any kind of light flickering. However, the output signal can be further optimized be changing the cut-off frequency of the low-pass filter.

The whole system has a power dissipation of 83.3 mW, in which the clock generator contributes with almost 90 % of this value. This high power consumption value is mainly due to the use of plenty inverting stages which are switching at a relatively high frequency (as aforementioned, the frequency division only happens after the ring oscillator). Adding the fact that in this kind of technology, where only n-type TFTs are used, the inverters are always consuming current during the system operation, unlike CMOS technology where the consumption only occurs during the state transitions

It is important to emphasize that for all blocks presented in the previous sections, operating frequencies of at least tens of kHz were achieved.

As aforementioned, all building blocks were also simulated using a V_{ON} of 0.5 V, and the results were essentially equal to the ones presented, only some biasing conditions were changed, this allow to guarantee a high circuit robustness even if some variations of the fabrication process





arise. However, in order to validate all the simulations, the proposed circuits will be fabricated and tested under the same simulated conditions.

4.3 Printed circuit board design

In order to realize the electrical characterization of blocks that need more than five source measure units (SMUs) there is a need to use PCBs to help both in the testing phase, in the debugging and also because the in-house parameter analyzers only have up to four micropositioners. All the PCBs were designed in CadSoft EAGLE software and for testing purposes there was also a need to design the layout of a PCI connector in order to make the connection between the substrate of the testing circuit and the respective PCB.

All the individual blocks will be further electrically characterized as well as the total system, so according to the inputs, outputs and biasing needed to each block, it was inferred that there was a need to design one PCB to each of the following blocks: capacitance-to-voltage converter, positive feedback differential amplifier, latch and the smart bottle total system.

Capacitance-to-voltage converter

Figure 7.1 in C annex, shows the schematic and the board of the PCB designed for the C/V converter testing. There was a need to design a circuit that would produce the non-overlapping phases for the switches as well as a buffer that allows the output signal measurement with an oscilloscope, since without this buffer the circuit performance would be degraded by the huge capacitance load of the oscilloscope probe.

Positive Feedback Differential Amplifier

The schematic and layout of the PCB designed for the positive feedback differential amplifier testing are presented in Figure 7.2 in C annex. It was necessary to design a circuit to produce two differential inputs, so two simple operational amplifiers (OPAMPs) inverting and non-inverting schemes were used. Hence, when fed by a wave generator the PCB will produce two perfectly differential waves. In this case we also need buffers at the output of the circuit to measure the signal for the same reason as above mentioned.

Latch

Regarding the latch, the designed PCB is almost equal to the one presented for the differential amplifier block since the testing requirements are quite similar, changing only the pins configuration. The schematic and layout of the PCB for this porpuse can be observed in figure 7.3 in C annex.





Full system

A PCB was also designed to test the entire system of the fill-level sensing bottle. Basically for this PCB several buffers were implemented in every important electrical node of the circuit, in order to help in the debugging by allowing to performe the signal measurement with an oscilloscope probe. The schematic and respective layout can be observed in figures 7.4 in C annex.





5 Conclusions and Future Perspectives

The work in this dissertation was focused on the development of a fully autonomous electronic system for a smart bottle packaging, taking into account all the circuitry involved for the desired application as well as the building blocks layouts and the auxiliary printed circuit boards to help in the testing phase.

Several building-blocks like a clock generator, a phase generator, a C/V converter and a comparator have been designed, being achieved good functionality and encouraging results for all of them. All the building-blocks can operate up to several tens of kHz, although in the final application a low frequency of operation will be used. Disregarding the clock generator, the system only comprises the reduced number of 55 TFTs, which is helpful concerning the random fabrication process variations that can occur resulting in device mismatches. In order to guarantee robustness against V_{ON} variations, all the system was re-simulated considering a value of 0.5 V instead of -0.5 V, and good results were also obtained by means of changing only some biasing conditions.

The C/V converter designed has shown to be quite interesting since a good sensibility of about 80 mV/pF was achieved, and a linear transfer characteristic was obtained for a range of few pF, using only a circuit with three TFTs and two capacitors (including the capacitive sensor) based on a charge distribution method, where no amplifying neither frequency or time conversion was used. Further adding up the fact that, no kind of reference was found regarding the use of oxide TFTs in designing any type of C/V converter.

The design and adaptation of the differential amplifier with positive feedback, to the a-IGZO TFT technology, allowed to proof the potential of this topology when a high gain is required in systems with low operating frequencies (since it has the drawback of having a lower bandwidth). Frequently used oxide TFT based differential amplifiers, like the common source topology allows to have gains in the order of 2-3 dB, while with this topology a gain of 20 dB was achieved [32].

Taking into account all the work involved, it is possible to conclude that oxide TFT technology has a huge and unexplored potential for many other low-frequency applications besides the mainstream and well-known backplanes of transparent displays or radio frequency identification tags (RFID) [33]–[36].

Since the masks layout and the testing PCBs were already designed, the fabrication in clean room environment and further electrical characterization of the whole system will occur during December 2016.

In terms of future circuit optimizations, the clock generator will most likely undergo some modifications since it consumes almost 90 % of the whole system power dissipation, and it has over twice the number of TFTs of the total remain building-blocks. A new approach with less ring oscillator stages must be pursuit, even if more frequency dividers are needed.





In the project final product, it is also desired to use a-ZTO TFTs instead of the mainstream a-IGZO due to some of the enhanced chemical and physical properties and the abundance of its elements in nature, resulting in low price, compared to a-IGZO, and favoring its widespread use. At the moment, one of the main drawbacks of a-ZTO TFTs is the lower electronic mobility when compared to the a-IGZO, but it doesn't make a huge difference in applications where operating speed is not such an important factor. Furthermore, owing to the higher electrical resistivity of ZTO compared to IGZO, harder saturation is achieved, resulting in higher intrinsic gain and better flexibility to design analog building-blocks

In the future, the layouts will also be moved from lab-scale processes to semi-industrial roll-to-roll systems (namely sputtering for the oxide semiconductor, atomic layer deposition for the dielectric and printing for the electrodes), allowing to enhance cheap, large scale, and mass production.

Lastly, although it was not yet developed, other features are desired to be integrated on the smart bottle, like a pressure sensor system to be used as an indicator of the pressure inside of the bottle to give consumers product quality information, for example, to understand if a carbonated drink is in optimal pressure for consumption and also a temperature sensor system to give consumers complementary information, namely if a drink is cold enough to be consumed.





6 References

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7 Annexes

Annex A – Design rules considered in each layer

Passivation layer

- Minimum separation of 10µm between two passivation layers.
- Minimum separation of 10µm for a notch made with passivation layer.
- Minimum width of 10µm for any object with Passivation layer.

Source/Drain layer

- Minimum separation of 10µm between two Source/Drain layers.
- Minimum separation of 10µm for a notch made with Source/Drain layer.
- Minimum width of 10µm for any object of a Source/Drain layer.
- Minimum overlap of 5µm between objects of Source/Drain and Semiconductor layers.
- Minimum overlap of 5µm between objects of Source/Drain and Gate layers.

Gate layer

- Minimum separation of 10µm between two Gate layers.
- Minimum separation of 10µm for a notch made with Gate layer.
- Minimum width of 10µm for the Gate layer.
- Minimum overlap of 5µm between objects of Gate layer and Source/Drain layers.

Semiconductor layer

- Minimum separation of 10µm between two Semiconductor layers.
- Minimum separation of 10µm for a notch made with Semiconductor layer.
- Minimum width of 10µm for the Semiconductor layer.

Metal 1 (M₁) hole layer

- Minimum separation of 20 μ m between two M₁ hole.
- Minimum width of 20µm for M₁ hole.
- Minimum enclosure of 15µm between Source Drain layer and the M₁ hole.
- Minimum enclosure of 15µm between the Gate layer and the M₁ hole.









Annex B - Transistor dimensions

It is important to refer that all the TFTs acting as diode-connected loads have a W/L dimension of $10/20~\mu m$, therefore they will not be considered in the following table.

Table 7.1- Transistor dimensions used in the final sizing of the smart-botlle system. (*) – The 3-input NAND used, has the same driving and load TFTs dimensions as the 2-input NAND.

Building- Blocks			Width (µm)	Length (µm)	Capaci- tance (pF)	Transistor Count
Ring Oscillator	Inverter	M_2	160	20	-	46
D-type Flip Flop	2-input NAND(*)	Мз	160	20	-	92
		M ₄	160	20	-	
Phase Generator	Inverter	Driving TFTs (from first to fourth in- verter)	40,80,160,320	20	-	24
	NOR	M ₅	320	20	-	
		M ₆	320	20	-	
		M_7	80	20	-	3
C/V Converter		Мв	80	20	-	
		M_9	80	20	-	
		Csensor	-	-	6	
		Cref	-	-	5-10	
Latch	Latch	$M_{10a,b}$	10	10	-	6
		M _{11a,b}	160	10	-	
	Double-to-single ended converter	$M_{12a,b}$	160	10	-	
		M _{13a,b}	80	20	-	
Differential Amplifier		$M_{14a,b}$	40	20	-	10
		M _{15a,b}	70	20	-	
		$M_{16a,b}$	80	20	-	
		M _{17a,b}	160	20	-	
Low-pass Fil- ter		M_{18}	10	20	-	1
		C ₁	-	-	150	









Annex C – Printed circuit boards schematics and layouts

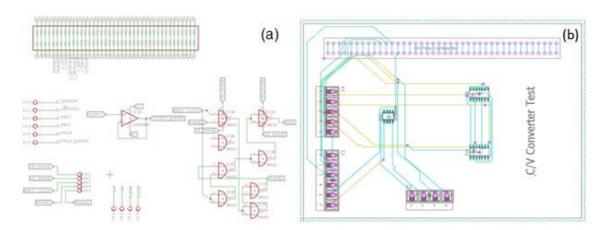


Figure 7.1- PCB schematic (a) and layout (b) for testing the capacitance-to-voltage converter.

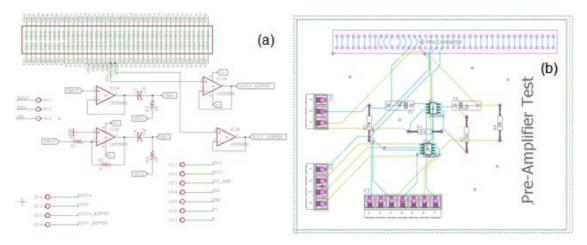


Figure 7.2- PCB schematic (a) and layout (b) for testing the positive feedback differential amplifier.





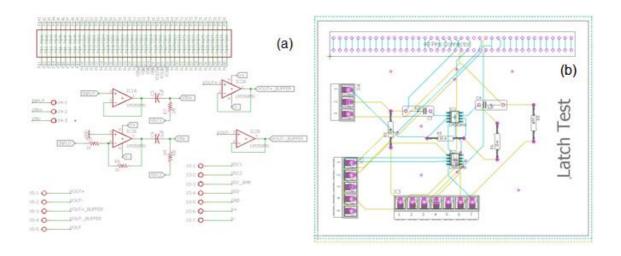


Figure 7.3- PCB schematic (a) and layout (b) for testing the latch.

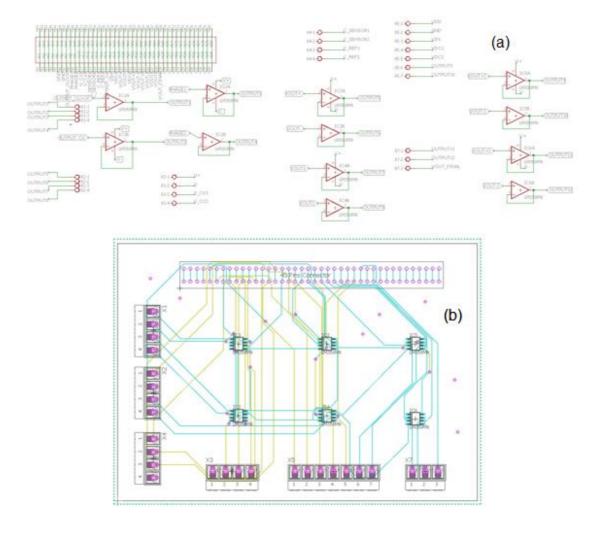


Figure 7.4- PCB schematic (a) and layout (b) for testing the smart botlle system.



